

Supporting Information

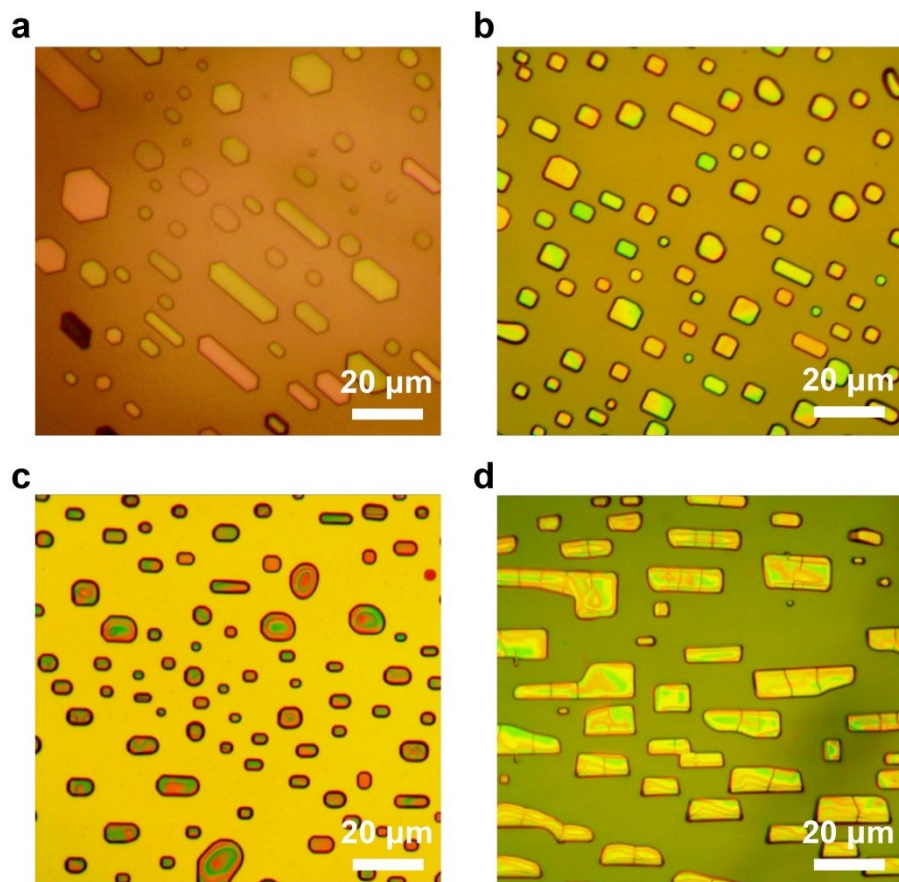
## Dual-source vapor-processed blue-emissive cesium copper iodine microplatelets with high crystallinity and stability

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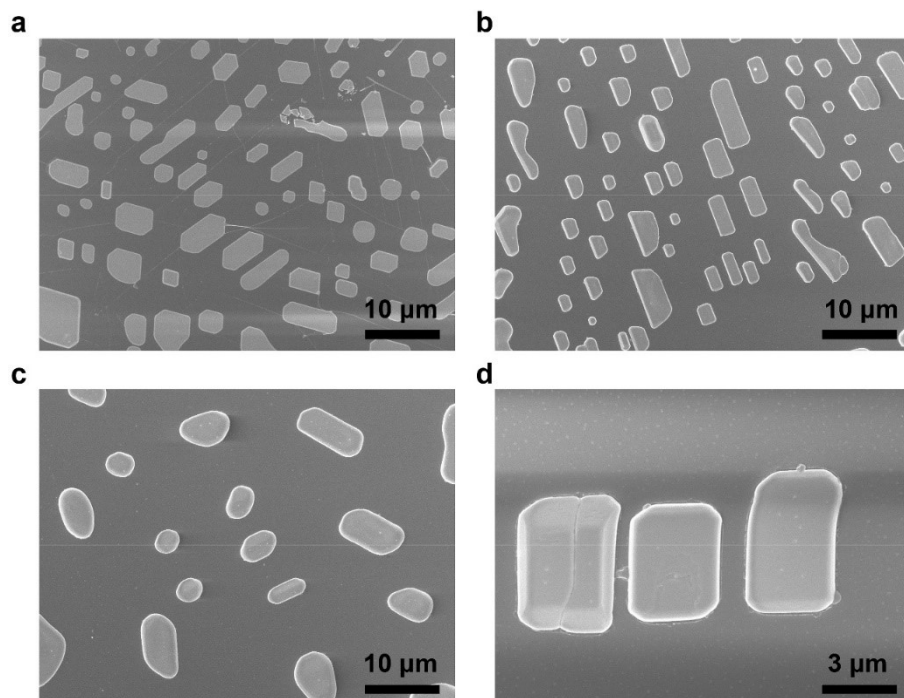
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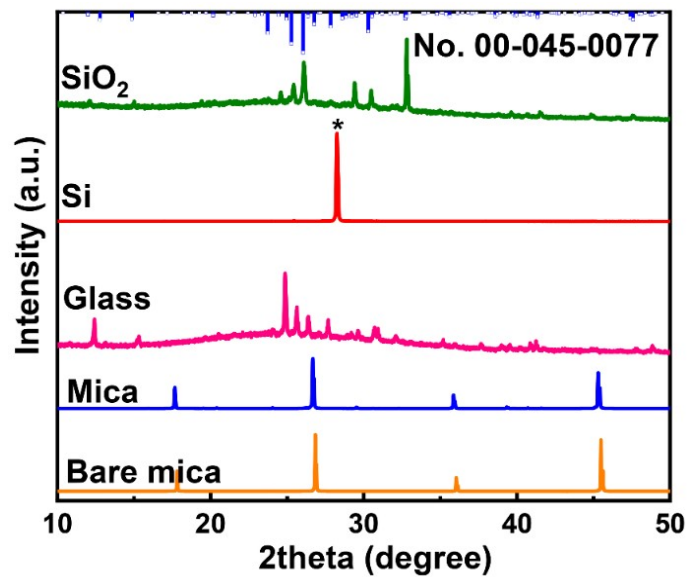
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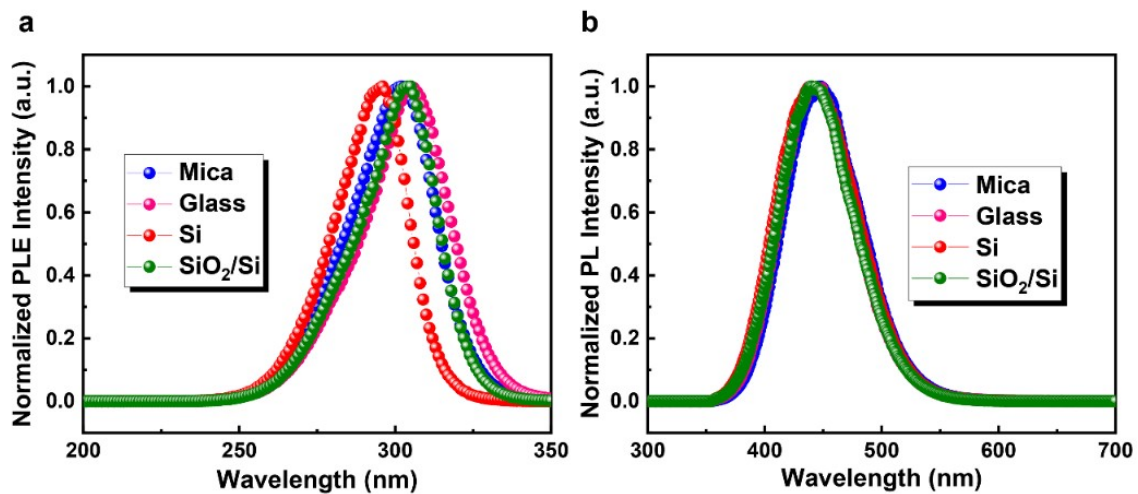
**Fig. S1.** Optical images of the Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub> microplatelets grown on (a) mica, (b) glass, (c) Si, and (d) SiO<sub>2</sub>/Si substrates, respectively.



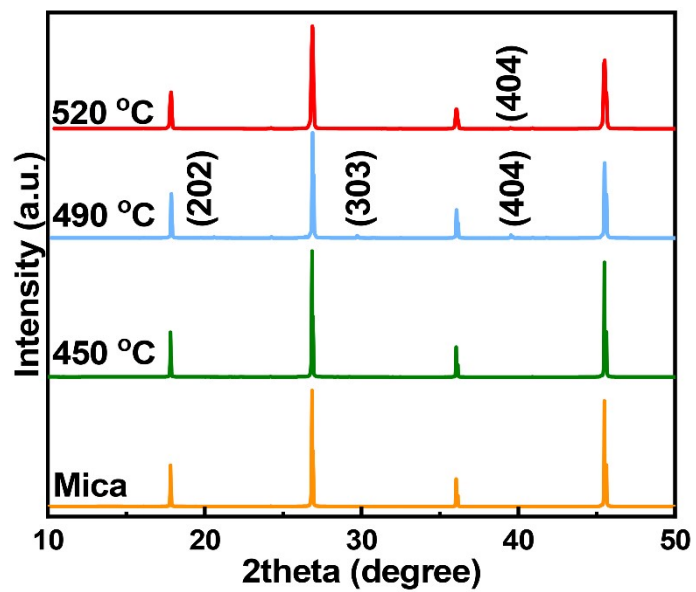
**Fig. S2.** SEM images of the  $\text{Cs}_3\text{Cu}_2\text{I}_5$  microplatelets grown on (a) mica, (b) glass, (c) Si, and (d)  $\text{SiO}_2/\text{Si}$  substrates, respectively.



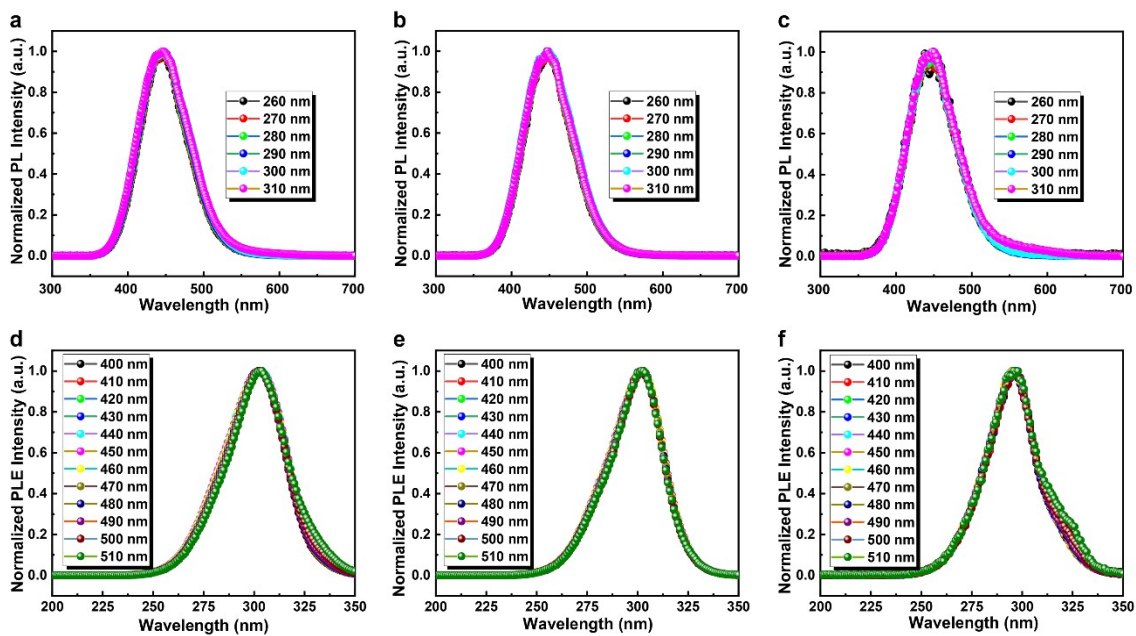
**Fig. S3.** XRD patterns of  $\text{Cs}_3\text{Cu}_2\text{I}_5$  microplatelets grown on mica, glass, Si (\* represents the diffraction peak of Si) and  $\text{SiO}_2/\text{Si}$  substrates.



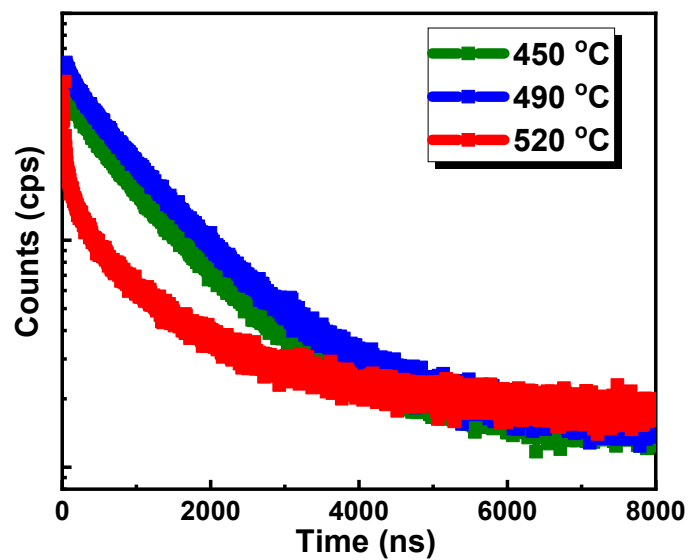
**Fig. S4.** (a) PL excitation spectra and (b) PL, of the  $\text{Cs}_3\text{Cu}_2\text{I}_5$  microplatelets grown on mica, glass, Si, and  $\text{SiO}_2/\text{Si}$  substrates, respectively.



**Fig. S5.** XRD patterns of  $\text{Cs}_3\text{Cu}_2\text{I}_5$  microplatelets prepared at different growth temperatures.

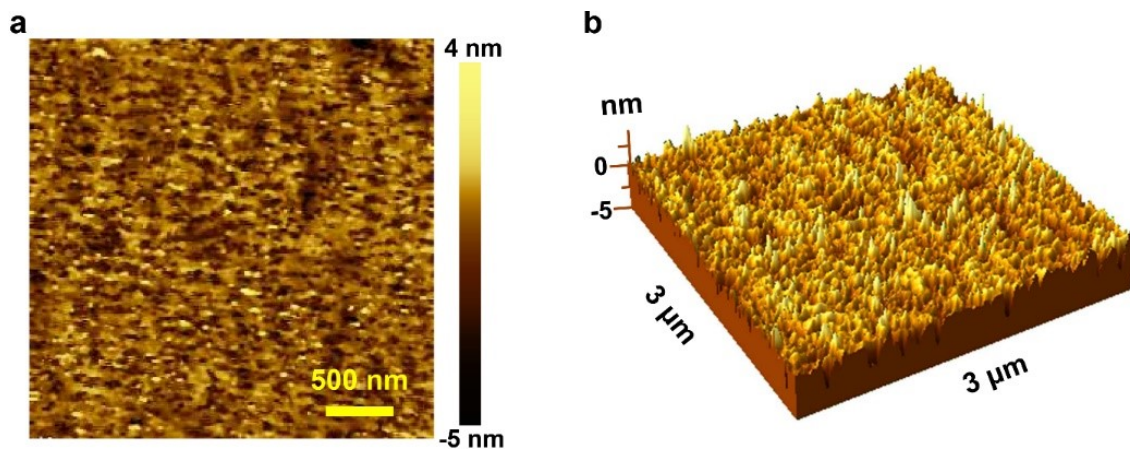


**Fig. S6.** PL spectra and PL excitation spectra of  $\text{Cs}_3\text{Cu}_2\text{I}_5$  microplatelets grown at different temperatures measured at different excitation and emission wavelengths, respectively. (a, d), 450 °C; (b, e) 490 °C; (c, f) 520 °C.

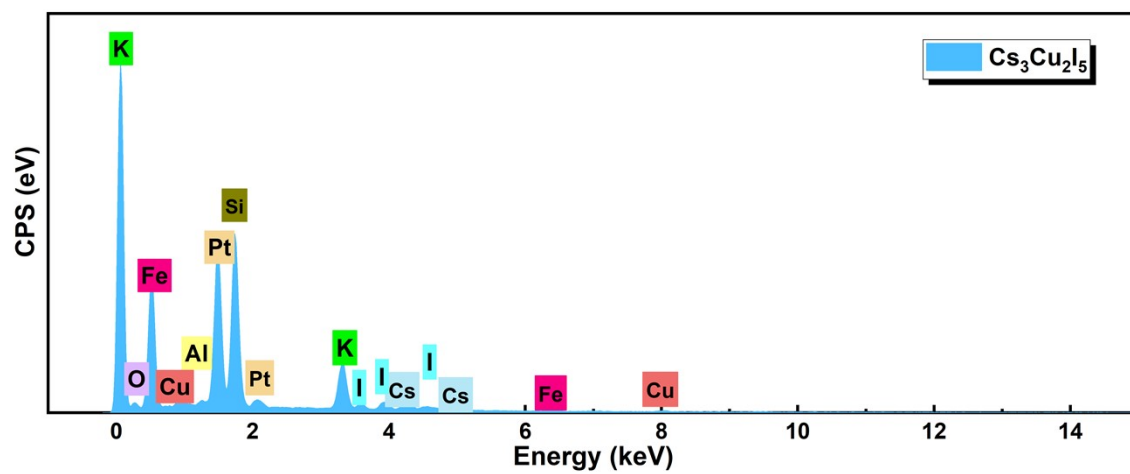


**Fig. S7.** PL decay curves of the Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub> microplatelets prepared at different growth temperatures.

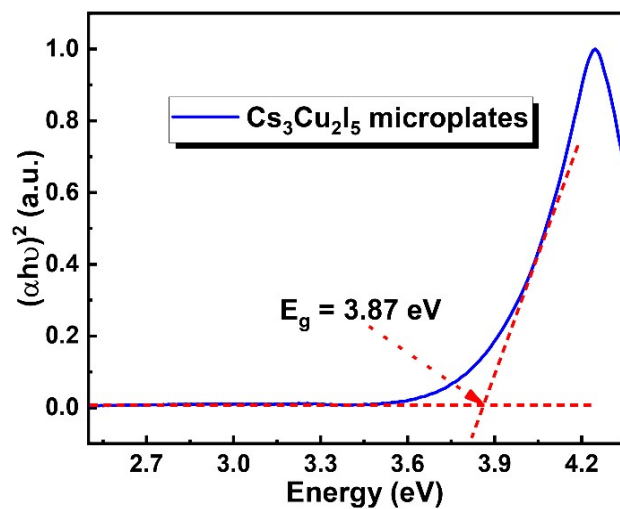




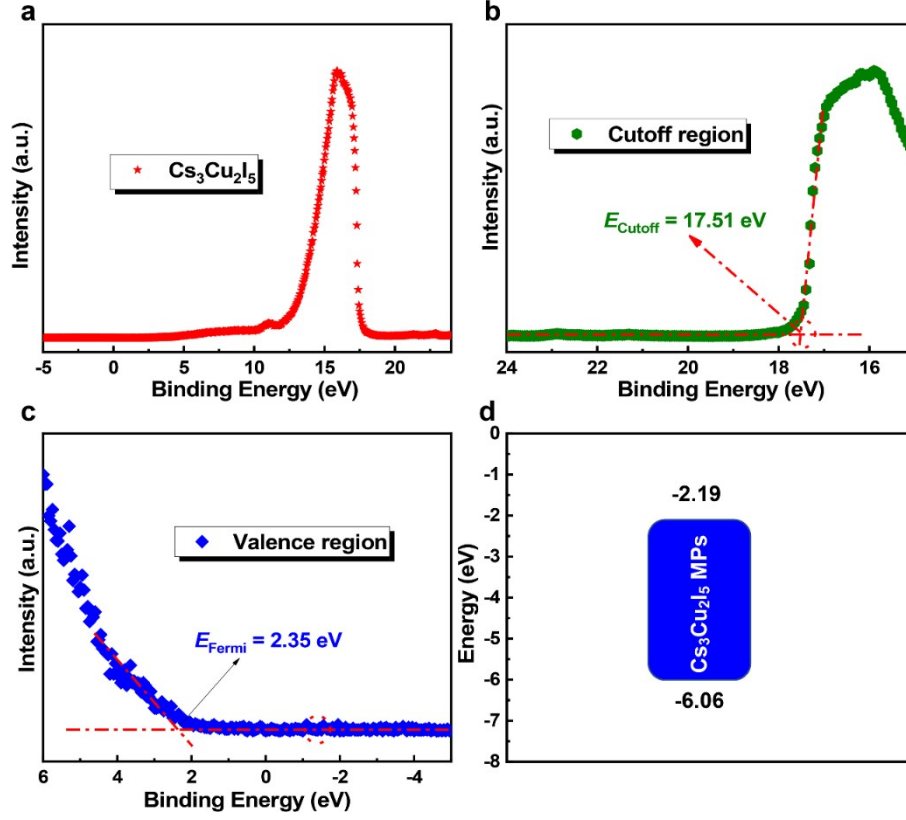
**Fig. S8.** AFM images of Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub> microplatelet on mica substrate.



**Fig. S9.** EDS spectrum of the  $\text{Cs}_3\text{Cu}_2\text{I}_5$  microplatelets.



**Fig. S10.** Tauc curve of the Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub> microplatelets corresponding to the absorption spectrum.



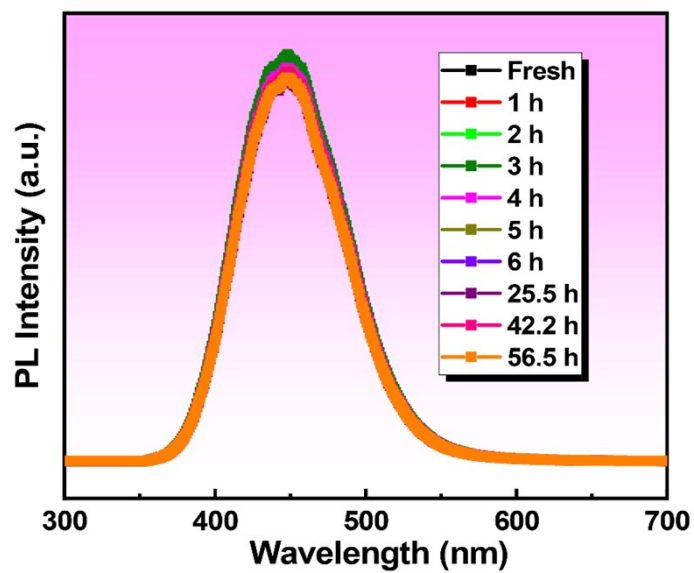
**Fig. S11.** UPS data of the Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub> microplatelets.

By means of the UV electronic energy spectrum (UPS), the  $E_{\text{Cutoff}}$  of the Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub> microplatelets is calculated as 17.51 eV and  $E_{\text{Fermi}}$  is 2.35 eV, and the formula is as follows:

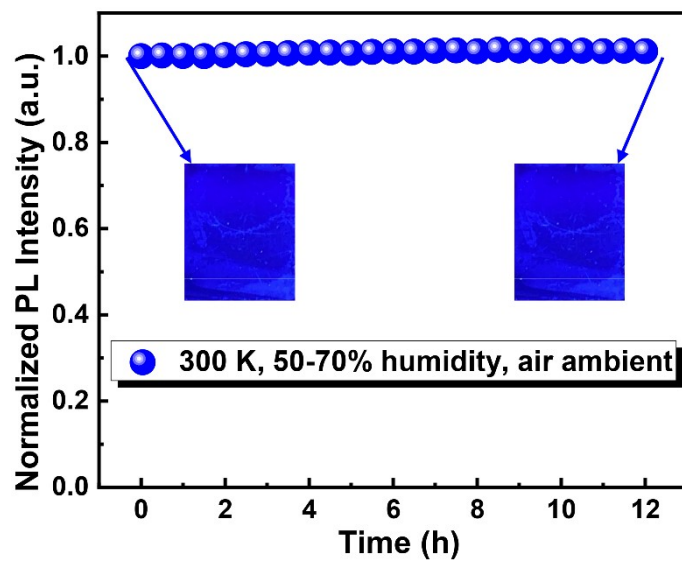
$$E_{\text{VBM}} = h\nu - E_{\text{Cutoff}} + E_{\text{Fermi}} \quad (1)$$

$$E_{\text{CBM}} = E_{\text{VBM}} + E_{\text{g}} \quad (2)$$

where,  $E_{\text{Cutoff}}$  is the binding energy of the secondary cutoff in the spectrum,  $E_{\text{Fermi}}$  is the difference between the valence band and Fermi energy level, and  $h\nu$  is the energy of a photon,  $E_{\text{VBM}}$  is the maximum price band,  $E_{\text{CBM}}$  is the minimum value of conduction band,  $E_{\text{g}}$  is the optical band gap of Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub>. After detailed calculation, the  $E_{\text{VBM}}$  and  $E_{\text{CBM}}$  of Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub> is 6.06 eV and 2.19 eV, respectively.



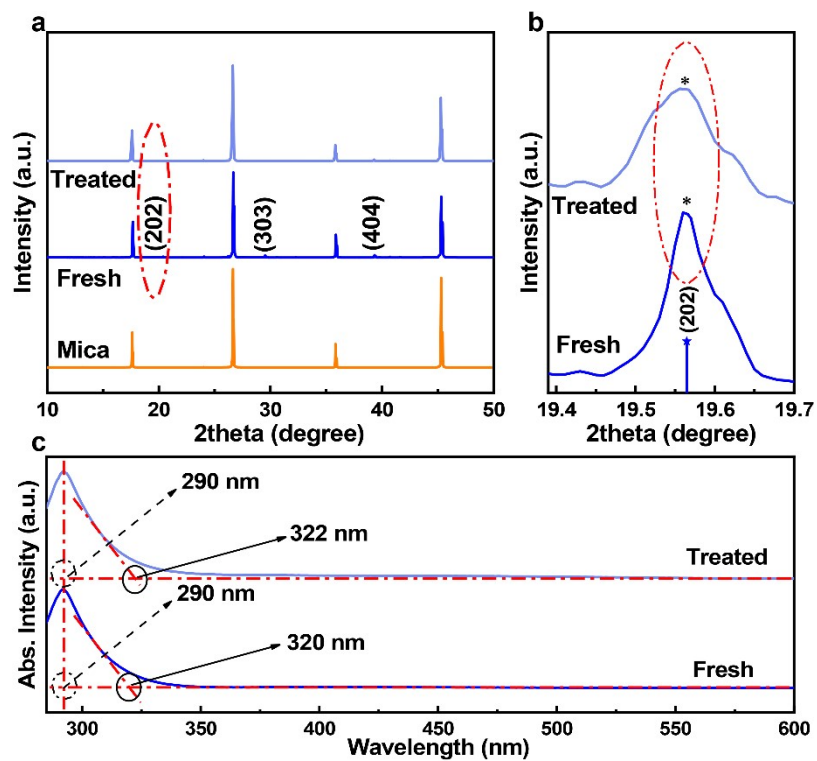
**Fig. S12.** Evolution of the PL spectra of the  $\text{Cs}_3\text{Cu}_2\text{I}_5$  microplatelet recorded under continuous UV light excitation (265 nm,  $3.4 \text{ mW/cm}^2$ ) in air ambient condition.



**Fig. S13.** Evolution of the PL intensity of the  $\text{Cs}_3\text{Cu}_2\text{I}_5$  microplatelets over a continuous test for

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h.



**Fig. S14.** Comparison on (a, b) the XRD patterns, and (c) UV-visible absorption spectra of the  $\text{Cs}_3\text{Cu}_2\text{I}_5$  MPs before and after humidity treatment in high humidity (90–95%) condition for 60 min.

**Table S1.** Fitting parameters of the PL decay curves for the Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub> microplatelets grown at different temperatures.

Growth temperature	$\tau_{\text{ave.}}$ (ns)	$\tau_1$ (ns)	$\tau_2$ (ns)	Percent ( $\tau_1$ )	Percent ( $\tau_2$ )	R <sup>2</sup>
450 °C	1012 ns	122.5 ns	1034.2 ns	17.2 %	82.8 %	0.999
490 °C	1072 ns	154.7 ns	1092.7 ns	13.5 %	86.5 %	0.999
520 °C	921 ns	104.8 ns	1081.0 ns	67.0 %	33.0 %	0.992



**Table S2.** Element compositions of the Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub> microplatelets with different morphologies.

Cs <sub>3</sub> Cu <sub>2</sub> I <sub>5</sub> microplatelets	Element	Weight (%)	Atomic (%)
3a-I	Cu K	2.35	0.93
	I L	11.32	2.26
	Cs L	6.43	1.22
3a-II	Cu K	1.61	0.59
	I L	7.15	1.32
	Cs L	3.74	0.66
3a-III	Cu K	3.24	1.40
	I L	14.6	3.16
	Cs L	8.41	1.73
3a-IV	Cu K	3.15	1.34
	I L	14.39	3.07
	Cs L	7.88	1.60

**Table S3.** Element compositions of the Cs<sub>3</sub>Cu<sub>2</sub>I<sub>5</sub> microplatelet.

Element	Weight (%)	Atomic (%)
Cu K	0.59	0.20
I L	3.48	0.58
Cs L	1.85	0.30